



2.1

1

0.1 mm 가 (phase contrast), (differential interference), brew - ster angle, confocal, infrared, Raman

(spherulite) (μm) (Optical Microscopy: OM) SPM

(nm) 가 4 nm (Scanning Electron Microscopy: SEM) 0.3 nm 가 SPM

Microscopy: SPM) (Scanning Probe TEM (contrast) 가 SEM

(high resolution TEM : HR - TEM) 가 SEM

, SPM TEM SEM

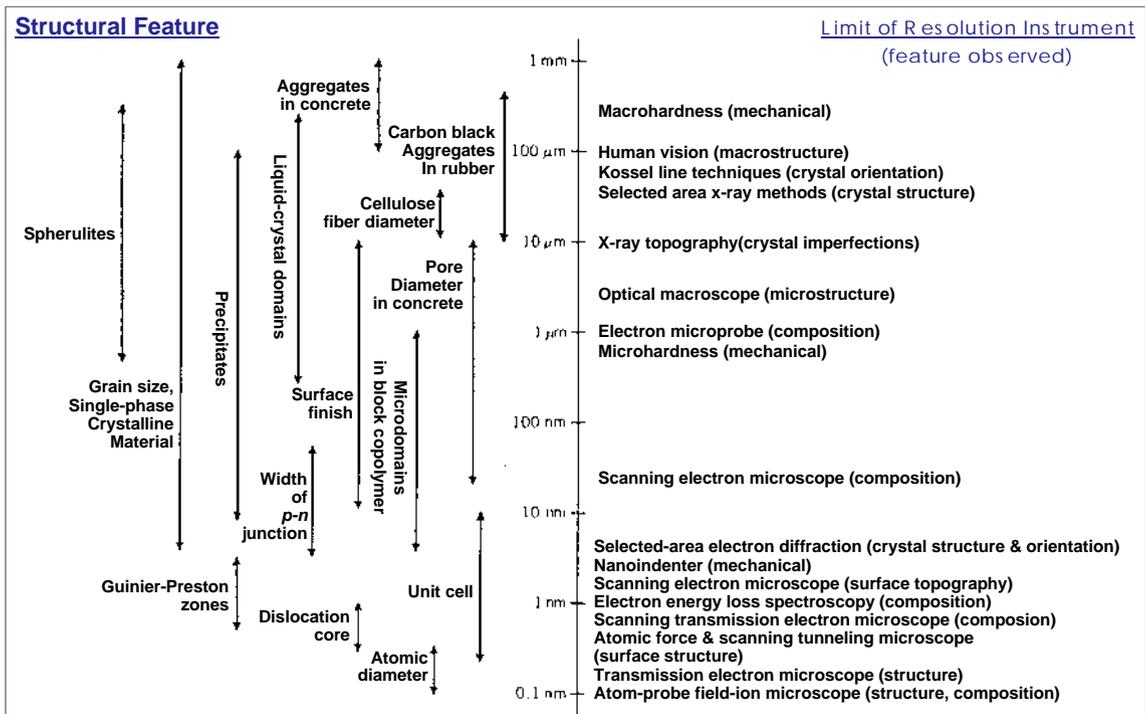
가 electron detector가 (secondary electron backscattered electron) SPM

ding lamellae , lamellae Atomic Force Mi -

HR - TEM SPM 가 . microscopy (AFM) TEM

500 nm ,

가 , near - field scanning

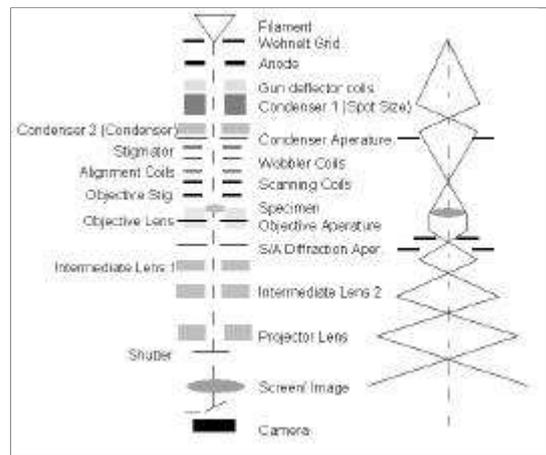


1.

1.

Technique	OM	SEM	TEM	AFM
Resolution	300 nm	10 nm	0.2 nm	0.3 nm
Magnification range	2 - 2000	20 - $1 \times 10^5$	200 - $2 \times 10^6$	1000 - $2 \times 10^6$
Can observe	surface, or bulk if transparent	Surfaces only	'bulk', but very thin films, less than 0.2 mm	surface
Specimen environment	ambient	High vacuum	High vacuum	Ambient, high Vacuum or fluid
Radiation damage	none	little	severe	none
Specimen preparation	easy	easy	very difficult	easy
Chemical analysis	no, unless connected to $\mu$ Raman	yes, X - ray	yes, X - ray and electron Energy loss	no
Can detect molecular orientation	yes	no	yes	no

가  
TEM  
가  
TEM  
가 가  
(electron dif -  
fraction:ED)  
lyotropic system 가  
가 1



2. TEM

2.2 TEM  
TEM

(objective lens)

( 2).  
LaB<sub>6</sub>  
Field Emission Gun (FEG)  
FEG 가

가 TEM

50 - 100 가

가  
가 가  
(condenser lens)  
X - Y  
(tilt) 가

2.3 (TEM Resolution)

TEM

가

$$d_{diff} = \frac{0.61\lambda}{a} \quad (1), \quad d_{chromatic} = C_c a \frac{\Delta E}{E} q_{max} \quad (2),$$

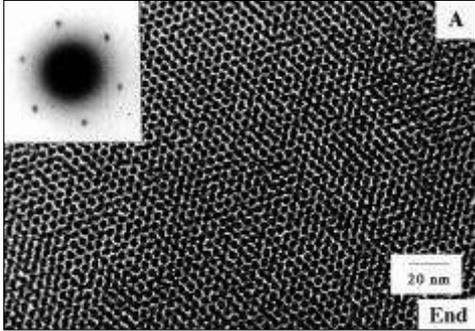
$$d_{spherical} = C_s a^3 \quad (3)$$

,  $\lambda$ : ,  $\alpha$ :

가 tilt 2  
3 가

,  $C_c$  : chromatic aberration constant,  $C_s$  : spherical aberration constant, E :

가 , 가  
 가 가  
 Chromatic (aberration)  
 100 eV  
 1 eV 0.2 nm  
 (spherical abera-  
 tion) TEM  
 , TEM 가  
 , 400 kV 가 0.17  
 nm 가 가 500  
 kV MV 가 (~0.1  
 nm)



3. Mass contrast phase contrast  
 hexagonal : Inset ED  
 RuO<sub>4</sub> staining mass contrast 가 , col-  
 umn 가 . TEM  
 solution spreading

2.4 (Contrast Mechanism)  
 가  
 contrast  
 . Contrast mass contrast, dif-  
 fraction contrast, phase contrast  
 Mass contrast  
 (beer's  
 ), , staining  
 contrast 가  
 Staining 가 가  
 가  
 , contrast 가  
 . Diffraction contrast  
 contrast가 phase  
 contrast  
 contrast  
 , contrast 가  
 가  
 가 contrast 가  
 가  
 lamellae, hexagonal, cubic  
 contrast mass contrast phase con-  
 trast가 ( 3). Staining  
 phase  
 contrast가 contrast

bilayer  
 contrast가  
 phase  
 contrast가  
 (phase shift)  
 contrast  
 function , contrast fo-  
 cusing  
 contrast가 가 focus in-focus  
 under-focus

2.5  
 TEM  
 ~50 nm  
 TEM  
 1) Thin Solid Film  
 - Solution Casting :  
 - Surface Tension Spreading :  
 ( , phosphoric acid)

- Solution or Melt Drawing :  
 가 drawing ,  
 poly(acrylic acid) replica .
- 2) Microtome: diamond knife  
 ~50 nm .
- 3) Collect Small Dispersed Objects  
 - Single Crystals : dilute solution  
 single crystal mica
- Clusters: TEM grid
- Ultrasonic fractures :  
 TEM grid .
- 4) Replica Surface : Poly (acrylic acid) salt  
 crystal ,

2. Staining Agents

Polymers	Stains
Unsaturated hydrocarbons, alcohols, ethers, amines	Osmium tetroxide
Acids or esters	(a) Hydrazine (b) Osmium tetroxide
Unsaturated rubber (resorcinolformaldehyde-latex)	Ebontite
Saturated hydrocarbons (PE and PP)	Chlorosulfonic acid/uranyl acetate
Amides, esters and PP	Phosphotungstic acid
Ethers, alcohols, aromatics, amines, rubber, bisphenol A and styrene	Ruthenium tetroxide
Esters, aromatic polyamides	Silver sulfide
Acids, esters	Uranyl acetate

가 가 가 . 가

가 ,

4 staining

low-dose smectic liquid  
 crystal layer ordering , phase  
 contrast contrast  
 layer .

2.6 Staining

TEM

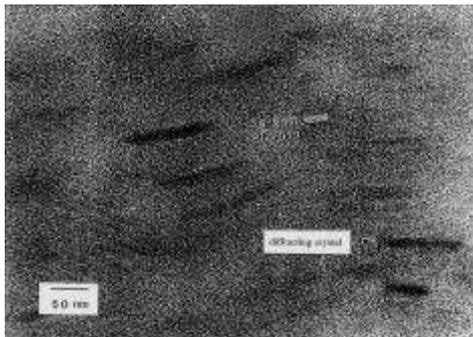
staining

low dose  
 가

ing . Staining  
 electron density contrast 가  
 . 2 staining

agent  
 negative staining 가  
 . Staining agent  
 가 staining agent

nm staining 가  
 가



4. Low dose smectic liquid crystal  
 layer ordering: staining 가 , staining  
 agent , 가 . Low dose  
 image , image contrast phase contrast  
 가 , surface tension spread-  
 ing .

2.7 Cryo-TEM & FF-TEM

가  
 TEM 가  
 , cryogenic TEM (cryo-TEM) freeze  
 fracture TEM (FF-TEM)  
 ( 3 ) . 가

grid, cryo-TEM, carbon, TEM, FF-TEM, replica, cryo-TEM, freeze-fracture, beam sensitive replica, beam sensitivity, cryo-TEM

3. FF-TEM cryo-TEM

FF-TEM

cryo-TEM

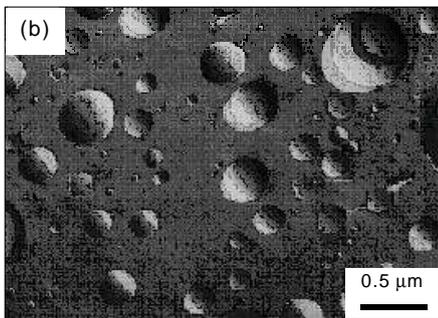
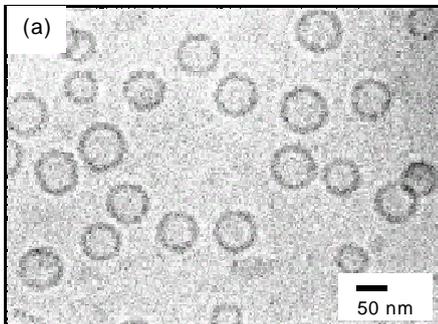
Multi-step sample preparation	Quick sample preparation
Viscous samples OK	Not suitable for viscous samples with long-length scale structures
Permanent replica of specimen; can be imaged many times	Delicate specimen; Can be imaged only once
Amplitude contrast	Phase contrast
Topographical image	Sample imaged in original state
Excellent depth resolution	Poor depth resolution; Structures appear superimposed

2 nm, Freeze-fracture replica, freeze-fracture, vesicle, cryo-TEM, FF-TEM

2.8 TEM

- 1) Electron beam damage,
- 2) sample preparation,
- 3) Interpretating images,
- 4) Sampling

TEM, Low dose, staining



5. (a) cryo-TEM bilayer : Replica (b) FF-TEM vesicle FF-TEM

, bulk, MV, tilt (ED), XRD, Nuetron Scattering (NS), ED, XRD

가 가 , stain -  
 ing 가 Staining  
 가 가

3.

Staining 가  
 low dose  
 5) 가 ,  
 6)  
 astigmatism lattice image

가 ,

1)

1. Jenny P. Glusker and Kenneth N. Trueblood, "Crystal Structure Analysis", Oxford Press, New York, 1985.

2)

2. S. M. Allen and E. L. Thomas, "The Structure of Materials", John Wiley & Sons, New York, 1999.

가  
 가  
 가

3. D. B. Williams and C. B. Carter, "Transmission Electron Microscopy: A Textbook for Materials Science", Plenum Press, New York, 1996.

70%

4. L. C. Sawyer and D. T. Grubb, "Polymer Microscopy", 2nd Ed., Chapman & Hall, New York, 1996.

3

confocal micro -

scopy near field optical microscopy

5. D. A. Bonnell, "Scanning Probe Microscopy and Spectroscopy: Theory, Techniques, and Applications", John and Wiley and Sons, New York, 2000.

가

scale limit

6. S. D. Hudson, H. T. Jung, V. Percec, W. - D. Cho, G. Johansson, G. Ungar, and V. S. K. Balagurusamy, *Science*, 278, 449 (1997).

3)

가

7. D. C. Martin and E. L. Thomas, *Polymer*, 36, 1743 (1995).

diffraction pattern

가

가

, TEM

8. H. - T. Jung, S. D. Hudson, and R. W. Lenz, *Macromolecules*, 31, 637 (1998).

ED

4) Beam sensitive

가

9. J. A. Zasadzinski and S. M. Bailey, *J. Electron Microscopy Technique*, 13, 309 (1989).